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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/053,865	01/18/2002	Mario Saggio	00-CT-320	5366	
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HOGAN & HARTSON LLP			EXAMINER		
1200 SEVENT			IM, JUNGHWA M		
DENVER, CO	80202		ART UNIT	PAPER NUMBER	
			2811	7_	
			DATE MAILED: 09/11/2002	T	

Please find below and/or attached an Office communication concerning this application or proceeding.

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	Application N	o. ,	Applicant(s)				
35 pp	10/053,865		SAGGIO ET AL.				
· Office Action Summary	Examiner		Art Unit				
•	Junghwa M. Ir		2811				
The MAILING DATE of this communic Period for Reply	ation appears on the co	er sheet with the c	orrespondence a	ddress			
A SHORTENED STATUTORY PERIOD FO THE MAILING DATE OF THIS COMMUNIC - Extensions of time may be available under the provisions of after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) - If NO period for reply is specified above, the maximum statules failure to reply within the set or extended period for reply within the set or extended p	ATION. f 37 CFR 1.136(a). In no event, hincation. days, a reply within the statutory yetory period will apply and will exp ill, by statute, cause the application.	owever, may a reply be tim minimum of thirty (30) day: ire SIX (6) MONTHS from in to become ABANDONE	nely filed s will be considered time the mailing date of this of	:ly. communication.			
1) Responsive to communication(s) file	d on 02 April 2002						
<u> </u>	b)⊠ This action is non	-final					
Since this application is in condition for closed in accordance with the practice Disposition of Claims	· — for allowance except for	formal matters, pr		ne merits is			
4) Claim(s) 1-9 is/are pending in the app	olication.						
4a) Of the above claim(s) is/are	withdrawn from consid	eration.					
5) Claim(s) is/are allowed.							
6)⊠ Claim(s) <u>1-9</u> is/are rejected.							
7) Claim(s) is/are objected to.							
8) Claim(s) are subject to restriction	on and/or election requi	rement.					
Application Papers							
9) The specification is objected to by the I	Examiner.						
10) The drawing(s) filed on is/are: a)□ accepted or b)□ obje	cted to by the Exar	niner.				
Applicant may not request that any object	ction to the drawing(s) be h	eld in abeyance. Se	ee 37 CFR 1.85(a).				
11) ☐ The proposed drawing correction filed on is: a) ☐ approved b) ☐ disapproved by the Examiner.							
If approved, corrected drawings are requ	ired in reply to this Office a	action.					
12) ☐ The oath or declaration is objected to b	y the Examiner.						
Priority under 35 U.S.C. §§ 119 and 120							
13) Acknowledgment is made of a claim for	or foreign priority under	35 U.S.C. § 119(a)	-(d) or (f).	•			
a)⊠ All b)□ Some * c)□ None of:							
1. Certified copies of the priority do	ocuments have been rec	ceived.					
2. Certified copies of the priority do	ocuments have been red	ceived in Application	on No				
Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)). * See the attached detailed Office action for a list of the certified copies not received.							
14) Acknowledgment is made of a claim for	domestic priority under	35 U.S.C. § 119(e) (to a provisional	l application).			
 a) The translation of the foreign language 15) Acknowledgment is made of a claim for 	•						
Attachment(s)							
1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTC 3) Information Disclosure Statement(s) (PTO-1449) Paper		Notice of Informal P	(PTO-413) Paper No atent Application (PT				
S. Patent and Trademark Office TO-326 (Rev. 04-01)	Office Action Summary		Part o	of Paper No. 7			

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DETAILED ACTION

Specification

The disclosure is objected to because of the following informalities:

On page 7, line 4, "/cm⁻²" should be corrected to /cm² or cm⁻².

Appropriate correction is required.

Claim Rejections - 35 USC § 112

The following is a quotation of the first paragraph of 35 U.S.C. 112:

The specification shall contain a written description of the invention, and of the manner and process of making and using it, in such full, clear, concise, and exact terms as to enable any person skilled in the art to which it pertains, or with which it is most nearly connected, to make and use the same and shall set forth the best mode contemplated by the inventor of carrying out his invention.

Claim 5 is rejected under 35 U.S.C. 112, first paragraph, as containing subject matter which was not described in the specification in such a way as to enable one skilled in the art to which it pertains, or with which it is most nearly connected, to make and/or use the invention.

Claim 5 recites the doped regions comprise doped regions that equalize the charges in the semiconductor material layer.

There is not a clear disclosure over what it means to equalize the charges in the semiconductor material layer, of how one of ordinary skill would accomplish such a result, or of how one of ordinary skill would know when "charges" have been "equalized".

Also, a term, "the charges" is not clear. Are these mobile charge carriers, fixed charges in the lattice, or both? What is meant by "equalizing" the "charges"?

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Claim Rejections - 35 USC § 112

The following is a quotation of the second paragraph of 35 U.S.C. 112:

The specification shall conclude with one or more claims particularly pointing out and distinctly claiming the subject matter which the applicant regards as his invention.

Claims 1 and 6 are rejected under 35 U.S.C. 112, second paragraph, as being indefinite for failing to particularly point out and distinctly claim the subject matter which applicant regards as the invention.

Claim 1 recites a substrate region of a first conductive type formed "in" a semiconductor material layer of the same conductivity type. Figures show a substrate region is formed under or below the a semiconductor material layer.

It is not clear what is meant by a substrate region formed "in" a semiconductor material layer.

Claim 6 recites the limitation of "said" body region in claim 1.

There is insufficient antecedent basis for this limitation in the claim. Claim 1 does not recite a "body region".

Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

⁽e) the invention was described in-

⁽¹⁾ an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effect under this subsection of a national application published under section 122(b) only if the international application designating the United States was published under Article 21(2)(a) of such treaty in the English language; or

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(2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that a patent shall not be deemed filed in the United States for the purposes of this subsection based on the filing of an international application filed under the treaty defined in section 351(a).

Claims 1-6, 8 and 9 are rejected under 35 U.S.C. 102(e) as being anticipated by the disclosed prior art to Werner et al. (U.S. Pat. No. 6,184,545)

Regarding claim 1, Werner et al. show, in Fig. 2, Schottky barrier diode comprising: a substrate region (5) of a first conductive type (n) formed in a semiconductor material layer (4) of the same conductivity type (n);

a metal layer (2); and

at least two doped regions (8 or 10) of a second conductive type (p) formed on said semiconductor material layer, each one of said doped regions being disposed under said metal layer and being separated from the other doped region by the portions of said semiconductor layer.

Regarding claim 2, Werner et al. teach that conducting-state current flow is through zones (9), so zones must have a lower resistance than the doped regions (8), because current flows along the lowest resistance path (col. 4, lines 19-21).

Regarding claim 3, Werner et al. show, in Fig. 2, the substrate comprises a doping value (n^+) higher than a doping value of the semiconductor material layer (n^-) .

Regarding claim 4, Werner et al. show, in Fig. 2, the doped regions comprises respective body region (8).

Regarding claim 5, Werner et al. show the doped regions comprise doped regions that equalize the charges in the semiconductor material (col. 4, line 37-43).

The "charges" are read as mobile charge carriers which are "equalized" because the

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reference teaches that there are no positive carriers and no negative carriers.

Regarding claim 6, Werner et al. show, in Fig. 2, the body regions (8) comprises heavily doped body regions (10) having the same conductivity type (p) of the doped regions.

Regarding claim 8, Werner et al. show, in Fig. 2, the doped body regions (8) comprise P-type doped regions.

Regarding claim 9, Werner et al. show, in Fig. 2, the semiconductor material layer comprises an N-type semiconductor material layer.

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 1 and 7 are rejected under 35 U.S.C. 103(a) as being unpatentable over Werner et al.

Claim 1 has been discussed previously.

Regarding claim 7, Werner et al. show the most aspect of pending claim except that the semiconductor material comprises a resistivity value lower than five ohm-cm for a breakdown voltage higher than 200V.

However, it would have been obvious to one of ordinary skill in the art at the time of the invention made to have an intended resistivity value for a breakdown voltage recited in pending. claim, since it would have been held that where the general conditions of a claim are disclosed

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in the prior art, discovering the optimum or workable ranges involves only in routine skill in the art. In re Aller, 105 USPQ 233

Higher breakdown voltage would have been obvious in order to allow device operation at higher voltages.

Claim Rejections - 35 USC § 102

Claims 1-9 are rejected under 35 U.S.C. 102(e) as being anticipated by the disclosed prior art to Bridge-Butler et al. (EP 0975024)

Regarding claim 1, Bridge-Butler et al. show, in Fig. 1, Schottky barrier diode comprising:

a substrate region (31) of a first conductive type (n) formed in a semiconductor material layer (32a) of the same conductivity type (n);

a metal layer (37); and

at least two doped regions (33a) of a second conductive type (p) formed on said semiconductor material layer, each one of said doped regions being disposed under said metal layer and being separated from the other doped region by the portions of said semiconductor layer.

Regarding claim 2, as noted above, the current flow is along the path of the lowest resistance.

Regarding claim 3, Bridge-Butler et al. show, in Fig. 1, the substrate comprises a doping value (n⁺) higher than a doping value of the semiconductor material layer (n⁻).

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Regarding claim 4, Bridge-Butler et al. show, in Fig. 1, the doped regions comprises respective body region (32).

Regarding claim 5, Bridge-Butler et al. teach that the device includes substrate region (32) that is depleted in the OFF state (Abstract)

Regarding claim 6, Bridge-Butler et al. show, in Fig. 1, the body regions (33a) comprises heavily doped body regions (32) having the same conductivity type (p) of the doped regions.

Regarding claim 7, Bridge-Butler et al. teaches a 300V device. The material layer (32a) "comprises" regions such as 32b or 34 which have impurity concentrations high enough to give a resistivity of less than 50hm-cm (col. 10, lines 16-44).

Regarding claim 8, Bridge-Butler et al. show, in Fig. 1, the doped body regions (32) comprise P-type doped regions.

Regarding claim 9, Bridge-Butler et al. show, in Fig. 1, the semiconductor material layer (32a) comprises an N-type semiconductor material layer.

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Junghwa M. Im whose telephone number is (703) 305-3998. The examiner can normally be reached on MON.-FRI. 8:30AM-5:00PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Tom Thomas can be reached on (703) 308-2772. The fax phone numbers for the organization where this application or proceeding is assigned are (703) 308-7722 for regular communications and (703) 308-7724 for After Final communications.

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Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is (703) 308-0956.

JMI September 8, 2002

> Sara Crane Primary Examiner